



Image

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q61045

Fumiyoishi ONO

Appln. No.: 09/672,776

Group Art Unit: 1765

Confirmation No.: 2256

Examiner: Kin Chan Chen

Filed: September 29, 2000

For: COMPOSITION FOR POLISHING METAL ON SEMICONDUCTOR WAFER AND METHOD OF
USING SAME

STATEMENT OF SUBSTANCE OF INTERVIEW

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Please review and enter the following remarks summarizing the interview conducted on
December 29, 2003 and January 6, 2004:

REMARKS

The interview on December 29, 2004 was initiated by the Examiner, and therefore, no
further recordation by the Applicant is believed to be required. However, during the interview,
the following was discussed:

1. Brief description of exhibits or demonstration: None
2. Identification of claims discussed: 6, 8 and 9
3. Identification of art discussed: None
4. Identification of principal proposed amendments: The Examiner suggested
amending claim 6 to recite an end point less than 90% for the α -conversion ratio.

5. Brief Identification of principal arguments: None
6. Indication of other pertinent matters discussed: None

SUBSTANCE OF INTERVIEW
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7. Results of Interview: Applicants agreed to amend claim 6 to recite "87%", and the amendment was made by Examiner's Amendment.

It is believed that no petition or fee is required. However, if the USPTO deems otherwise, Applicant hereby petitions for any extension of time which may be required to maintain the pendency of this case, and any required fee, except for the Issue Fee, for such extension is to be charged to Deposit Account No. 19-4880.

Respectfully submitted,



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WASHINGTON OFFICE
23373
CUSTOMER NUMBER

Date: February 25, 2004